

Re: Deuterated bis (2-methoxyethyl)

Please be advised that the products listed below:

General Purpose Polystyrene (GPPS): **Resirene® HH-101, HH-103, HH-104, HH-108, HF-555 y HF-777**

High Impact Polystyrene (HIPS): **Resirene® 2210, 4220, 5470, 6110, 6420, 6470 y 7600**

Styrene-Acrylic Copolymers (SMMA): **CET® 116, CET®123, CET®230, CET® 240, CET® 250, CET® 265, CET® 231 DB, CET® 241 DB, CET® 251 DB**

do not contain Deuterated bis (2-methoxyethyl). Furthermore, Deuterated bis (2-methoxyethyl) cannot be formed as a by-product of our manufacturing process, as its chemical structure and properties are chemically unrelated to those of the raw materials used. Therefore, there is no plausible pathway for its formation from the raw materials involved in our process.

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Jorge F. Navarro
Regulatory Affairs – Product Stewardship
safety@resirene.com